



PATENT
2185-0343P

IN THE U.S. PATENT AND TRADEMARK OFFICE

Applicant: Yasunori UETANI et al. Conf.: 8929
Appl. No.: 09/323,230 Group: 1752
Filed: June 1, 1999 Examiner: J. Chu
For: A POSITIVE RESIST COMPOSITION

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PRELIMINARY AMENDMENT

Assistant Commissioner for Patents
Washington, DC 20231

April 16, 2001

Sir:

The following preliminary amendments and remarks are respectfully submitted in connection with the above-identified application.

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In the Specification:

Please replace the paragraph beginning on page 9, line 2, with the following rewritten paragraph:

The positive resist composition of the present invention comprises the novolac resin described above, quinonediazide compound and the thioxanthone compound as the essential ingredients. In addition, the positive resist composition of the present invention may comprise a resin other than the novolac resin, as well as a small amount of various additives conventional in this field, such as a dye, a surfactant and the like, as

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